



L Number	Hits	Search Text	DB	Time stamp
1	62271	(etch\$3 clean\$3) and (wafer substrate) and	USPAT;	2003/07/05 15:37
		(bath container tank)	US-PGPUB	
2	3382	((etch\$3 clean\$3) and (wafer substrate)	USPAT;	2003/07/05 15:38
		and (bath container tank)) and ((etch\$3	US-PGPUB	
		clean\$3) near10 (wafer substrate) near10		
		(bath container tank))		
4	2842	(((etch\$3 clean\$3) and (wafer substrate)	USPAT;	2003/07/05 15:38
		and (bath container tank)) and ((etch\$3	US-PGPUB	
i		clean\$3) near10 (wafer substrate) near10		
		(bath container tank))) and (liquid		
		solution)		
5	830	((((etch\$3 clean\$3) and (wafer substrate)	USPAT;	2003/07/05 15:38
		and (bath container tank)) and ((etch\$3	US-PGPUB	
		clean\$3) near10 (wafer substrate) near10	l .	
		(bath container tank))) and (liquid	İ	
		solution)) and ("HF" (hydrogn near		1
		fluoride) (hydro near3 fluoric near3		
		acid))		
6	7119	(etch\$3 clean\$3) and (wafer substrate) and	EPO; JPO;	2003/07/05 15:38
		(bath container tank)	DERWENT;	
ĺ			IBM_TDB	
7	2798	((etch\$3 clean\$3) and (wafer substrate)	EPO; JPO;	2003/07/05 15:38
		and (bath container tank)) and ((etch\$3	DERWENT;	
		clean\$3) near10 (wafer substrate) near10	IBM_TDB	
		(bath container tank))		İ
8	1722	(((etch\$3 clean\$3) and (wafer substrate)	EPO; JPO;	2003/07/05 15:38
		and (bath container tank)) and ((etch\$3	DERWENT;	
		clean\$3) near10 (wafer substrate) near10	IBM_TDB	
		(bath container tank))) and (liquid		
		solution)		
9	50	((((etch\$3 clean\$3) and (wafer substrate)	EPO; JPO;	2003/07/05 15:39
		and (bath container tank)) and ((etch\$3	DERWENT;	
		clean\$3) near10 (wafer substrate) near10	IBM_TDB	
		(bath container tank))) and (liquid		
		solution)) and ("HF" (hydrogn near		
		fluoride) (hydro near3 fluoric near3		
		acid))		